



PTO-1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO.	SERIAL NUMBER
	213.003-D3-US	10/763,433
	APPLICANT(S)	
	Ye et al.	
	FILING DATE	GROUP ART UNIT
	January 23, 2004	2857

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EXAMINER	<i>Edmond Raymond</i>	DATE CONSIDERED	7/1/04
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EXAMINER	<i>Adward J. Raymond</i>	DATE CONSIDERED	7/1/04
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Cut	WO 00/59206	10/2000	PCT			
Can	WO 02/17030	2/2002	PCT			

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EXAMINER	<i>Richard K. Fung</i>	DATE CONSIDERED	7/1/04
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